

	Type	L #	Search Text	DBs
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3	BRS	L3	(mask same writ\$4) and (design same data) and layer and opc and feature and context	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TD B

	Type	L #	Search Text	DBs
4	BRS	L4	(mask same writ\$4) and (design same data) and layer and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
5	BRS	L5	(mask same writ\$4) and (design same data) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L6	(mask near6 writ\$4) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Search Text	DBs
7	BRS	L7	(mask near6 writ\$4) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
8	BRS	L8	(mask same writ\$4) and (design same data) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
9	BRS	L9	(mask same writ\$4) and (design same data) and (multiple same layer) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Search Text	DBs
10	BRS	L10	(mask same writ\$4) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
11	BRS	L11	(mask same writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
12	BRS	L12	(mask near6 writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Search Text	DBs
13	BRS	L13	(mask near6 writ\$4) and opc and print and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
14	BRS	L14	(mask near6 writ\$4) and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
15	BRS	L15	(mask near6 writ\$4) and opc and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

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